

The sEKV Model for the Design of Cryo-CMOS Circuits

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- **Introduction**
- Subthreshold current and swing
- Threshold voltage
- Simplified EKV model at CT
- RF modeling
- Noise modeling
- Conclusion

Reduction of T down to Cryogenic Temperature (CT)

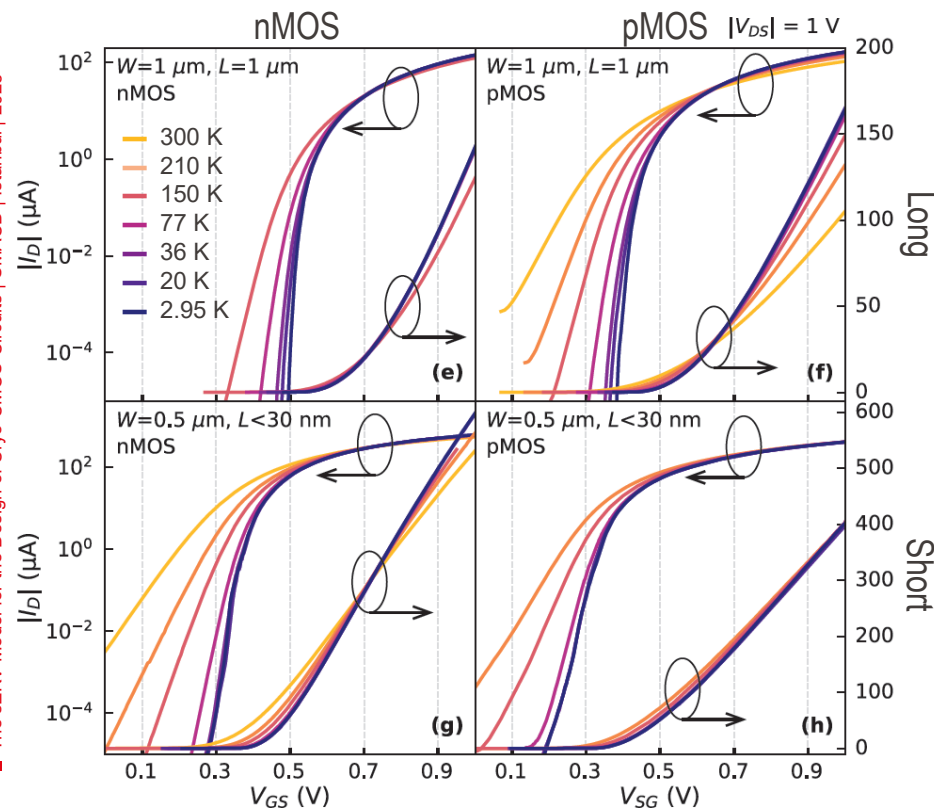
Parameter	CT Behavior	Impact
Mobility	Increases	😊
Saturated velocity	Increases	😊
Transconductance	Increases	😊
Subthreshold swing (SS)	Decreases, but saturates at LT	😊 😞
Leakage currents	Decrease	😊
Thermal conductivity	Increases	😊
Thermal noise	Decreases	😊
Flicker noise	Increases	😞
Threshold voltage	Increases	😞
Oscillations and kinks in the transfer and output characteristic	Appear	😞

Outline

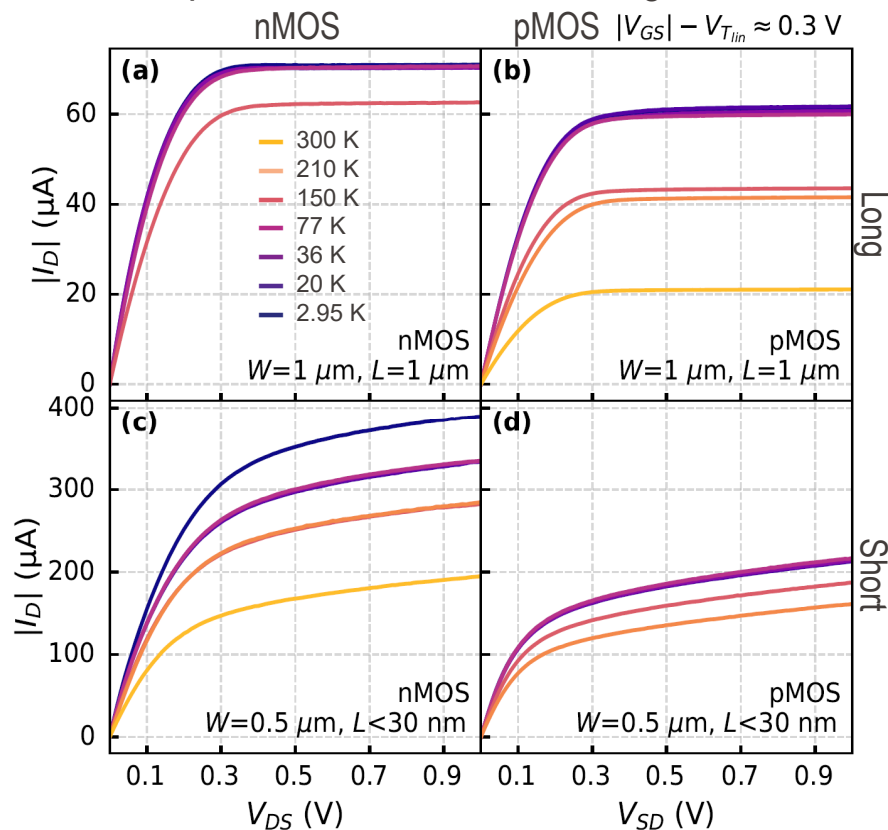
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I-V Characteristics of 22 nm FDSOI

Transfer Characteristic in Saturation

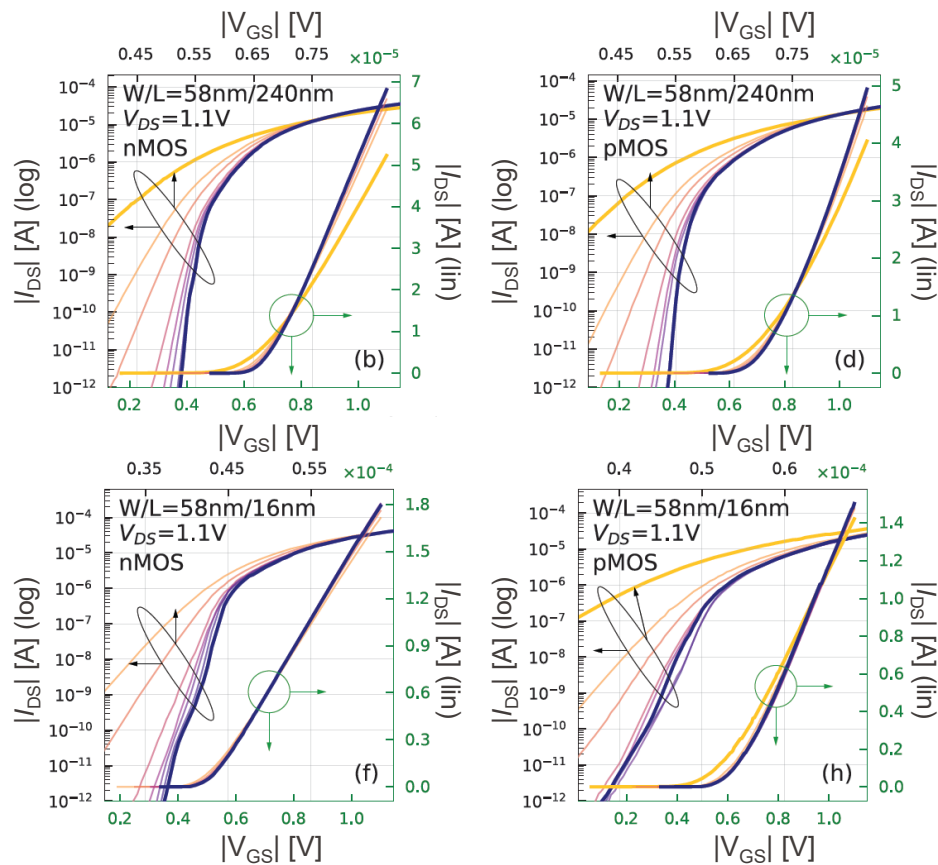


Output Characteristic in Strong Inversion

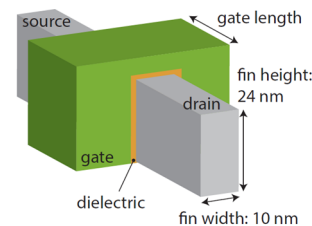
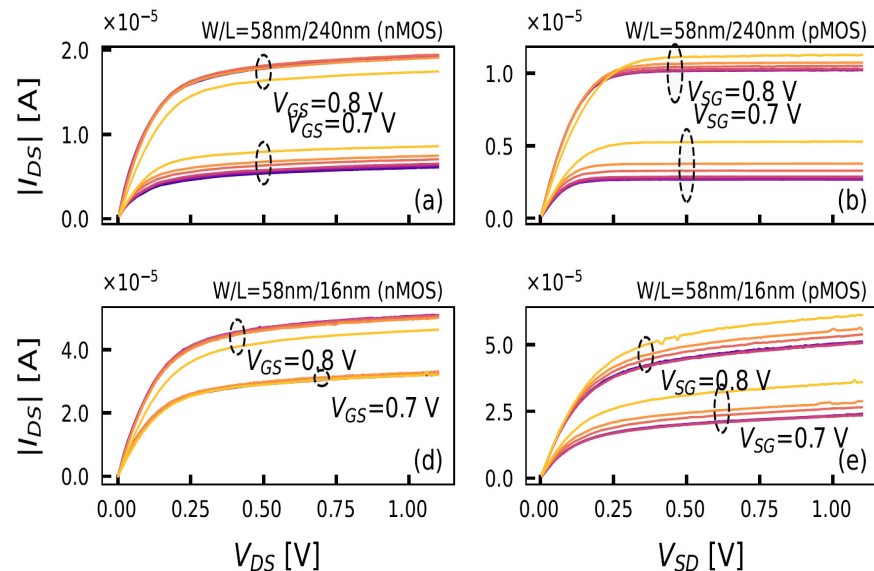


I-V Characteristics of 16nm FinFET

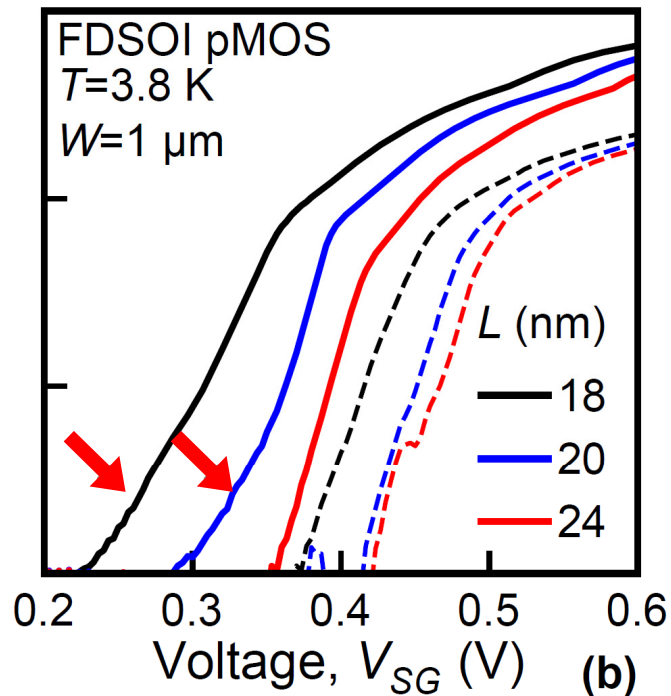
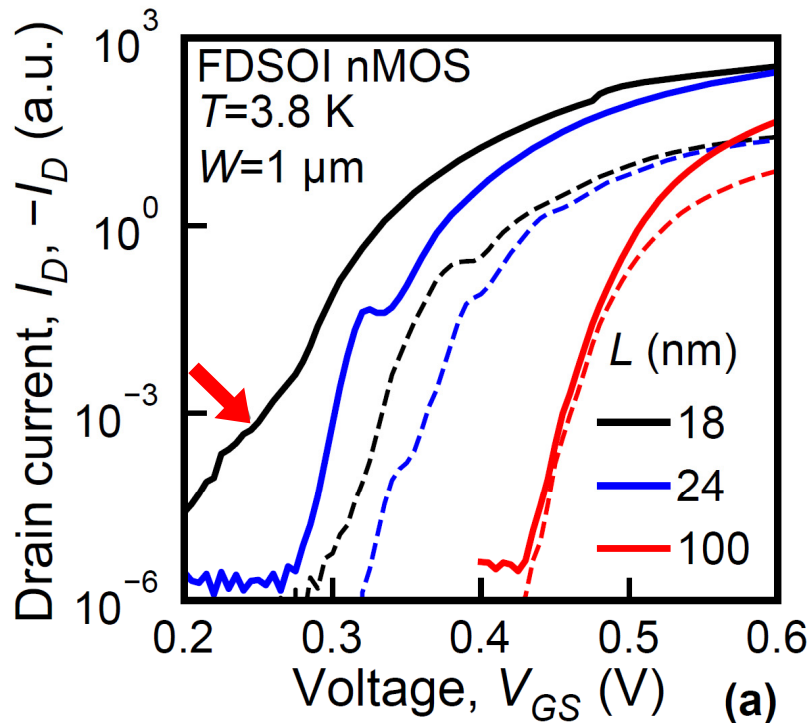
Transfer Characteristic in Saturation



Output Characteristic in Strong Inversion

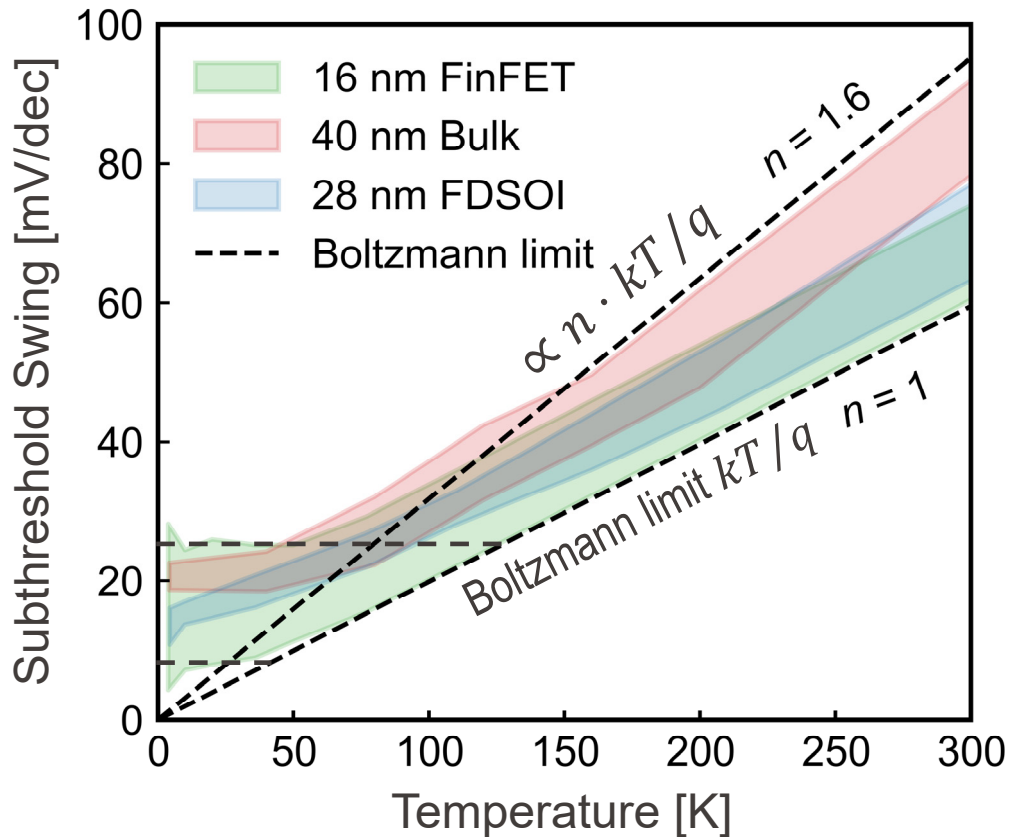


Subthreshold Current



Dashed lines: $V_{DS} = 10$ mV (linear)
Solid lines: $V_{DS} = 0.8$ V (saturation)

Subthreshold Swing SS



$$SS \triangleq \left(\frac{d \log_{10} I_D}{d V_G} \right)^{-1}$$

$$= \underbrace{\frac{\partial V_G}{\partial \varphi_{ch}}}_{\text{Electro static control}} \cdot \underbrace{\left(\frac{d \log_{10} I_D}{d \varphi_{ch}} \right)^{-1}}_{\text{Thermionic current}}$$

$$= n \cdot \ln 10 \frac{kT}{q}$$

Impact of SS Saturation on Power

- Required current to achieve a given **transconductance** G_m in weak inversion

$$I_D = G_m \cdot n_{eq} \cdot U_T$$

- with $U_T \triangleq \frac{kT}{q}$ and where n_{eq} is defined as

$$n_{eq}(T) = \frac{SS(T)}{\ln 10 \cdot U_T} = \begin{cases} n & \text{for } T_c < T \\ \frac{q}{\ln 10} \cdot \frac{SS_{sat}}{kT} & \text{for } T < T_c \end{cases}$$

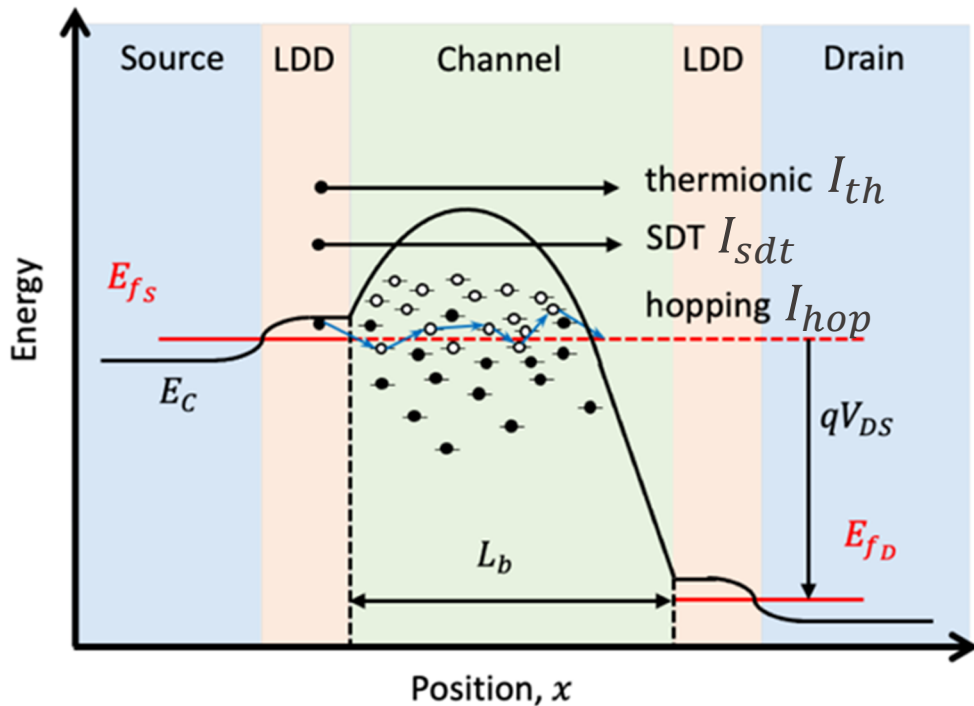
- Current savings** at CT to reach the same G_m than at RT in weak inversion

$$\frac{I_D|_{cryo}}{I_D|_{RT}} = \frac{n_{eq}|_{cryo}}{n_{eq}|_{RT}} \cdot \frac{T_{cryo}}{T_{RT}} = \frac{33}{1.5} \cdot \frac{4.2}{300} = 22 \cdot \frac{1}{71} = \frac{1}{3.2}$$

- Current savings of 3.2 instead of 70 if n_{eq} would remain constant

Subthreshold Drain Current

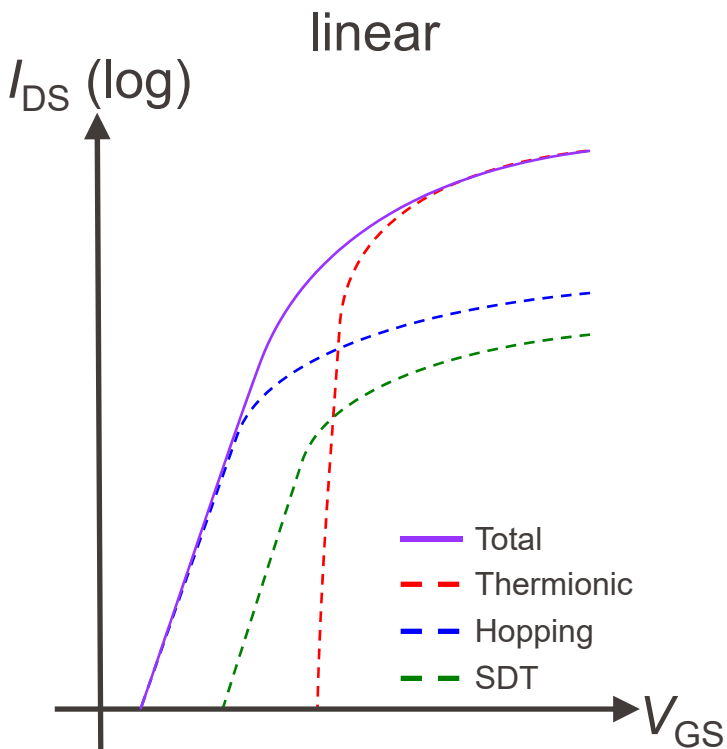
$$I_{sub} = I_{th} + I_{hop} + I_{sdt}$$



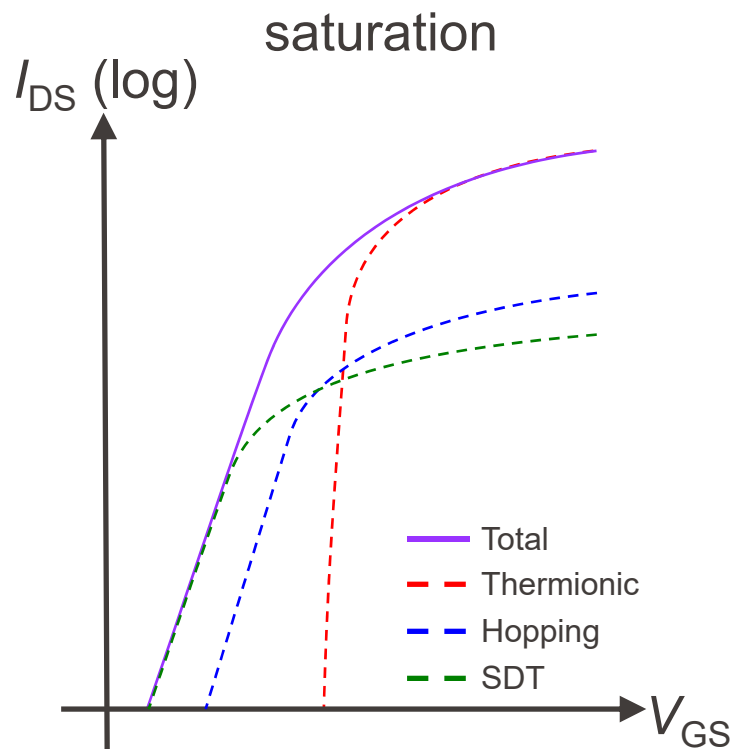
- The subthreshold drain current I_{sub} is made of

$$I_{sub} = I_{th} + I_{hop} + I_{sdt}$$
- The **thermionic current** I_{th} which dominates at RT
- The **hopping current** I_{hop} in band tail
- The **source-to-drain tunneling current** I_{sdt}

Subthreshold Currents at CT

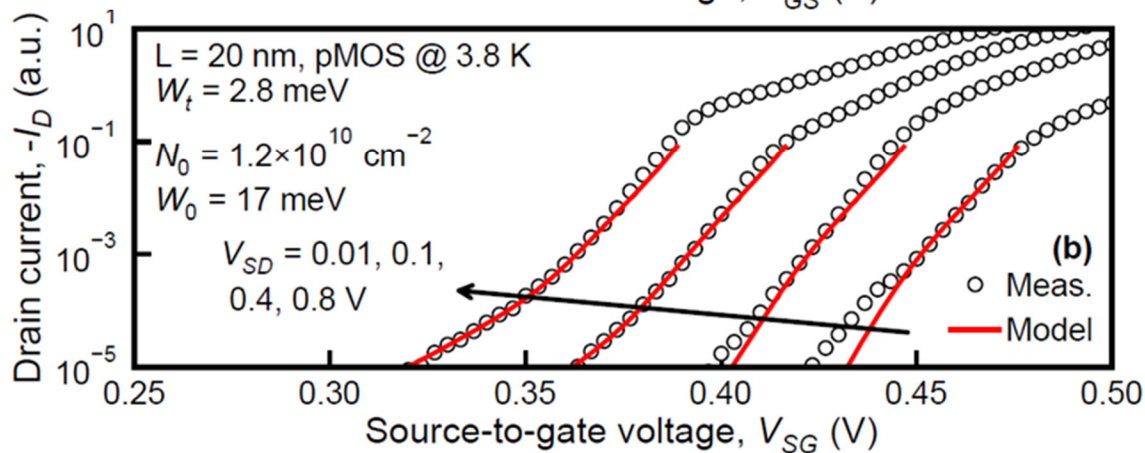
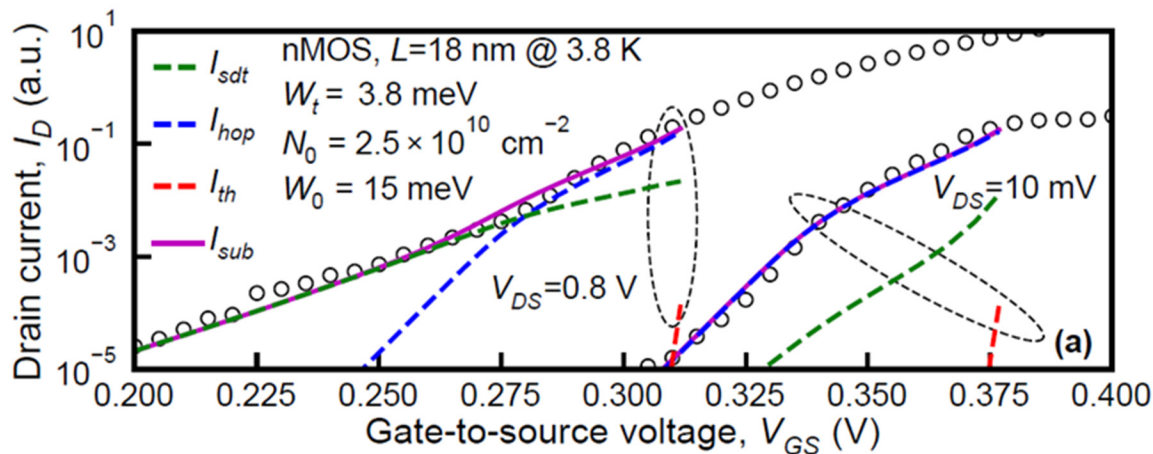


■ Hopping current dominates

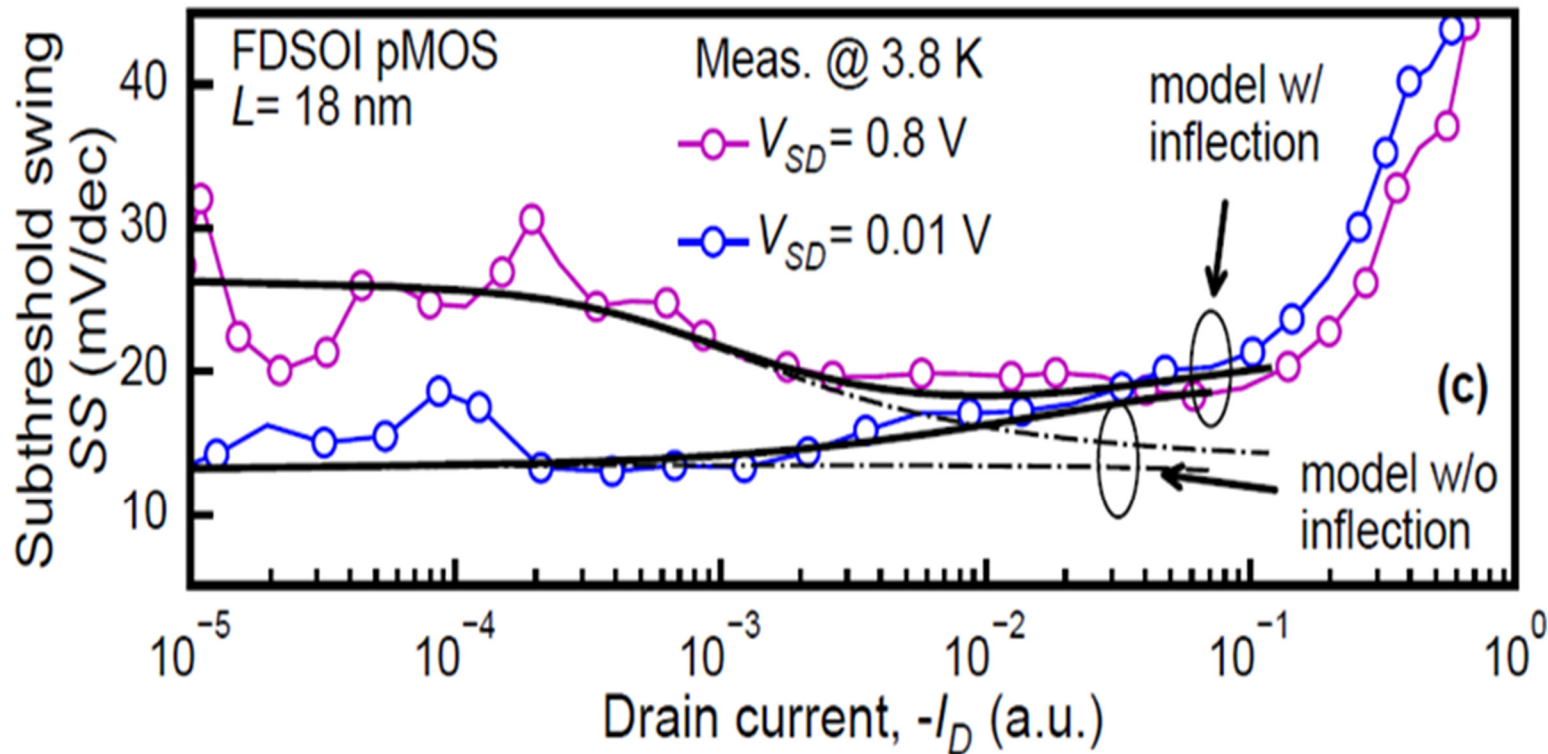


■ SDT current dominates

Subthreshold Current Model Validation on 22nm FDSOI at CT



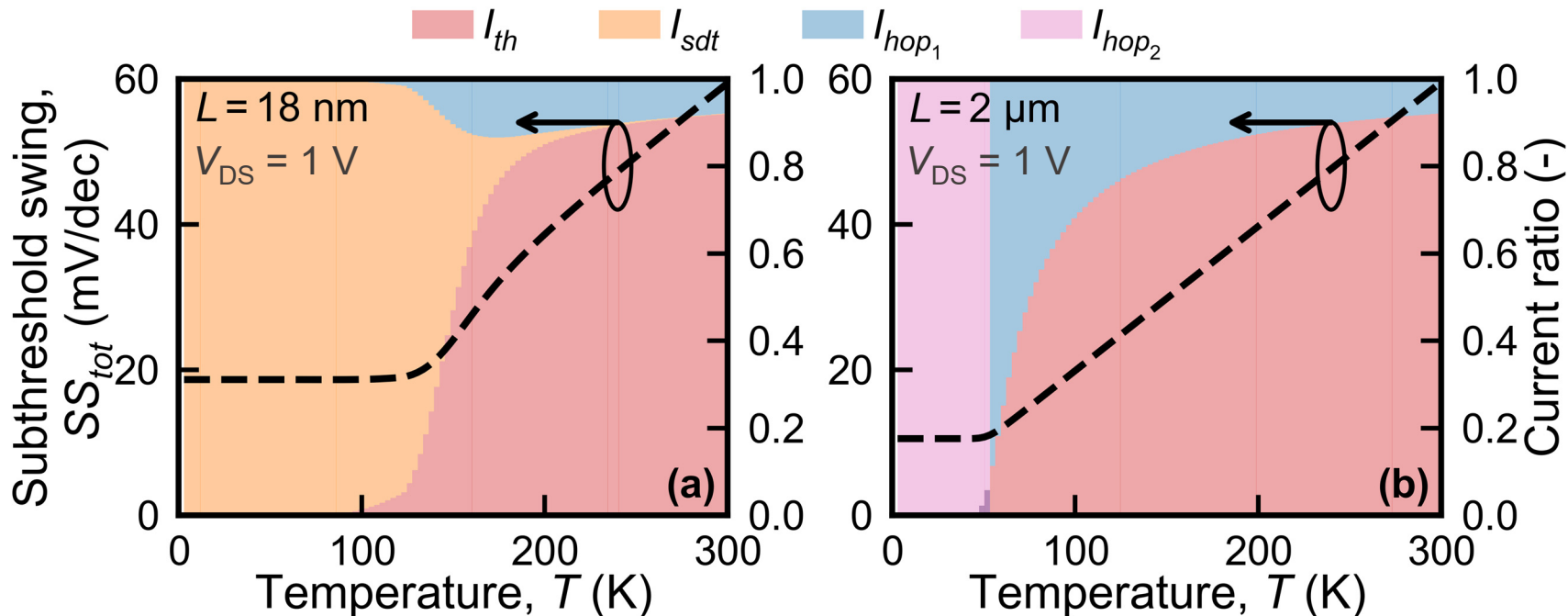
Subthreshold Swing Validation on 22nm FDSOI at CT



Current Decomposition and Subthreshold Swing

Short-channel in saturation

Long-channel in saturation



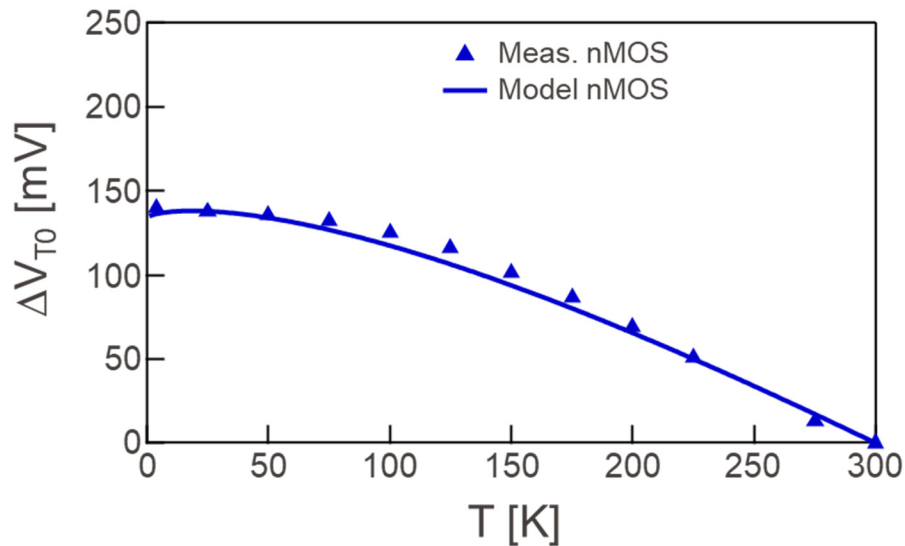
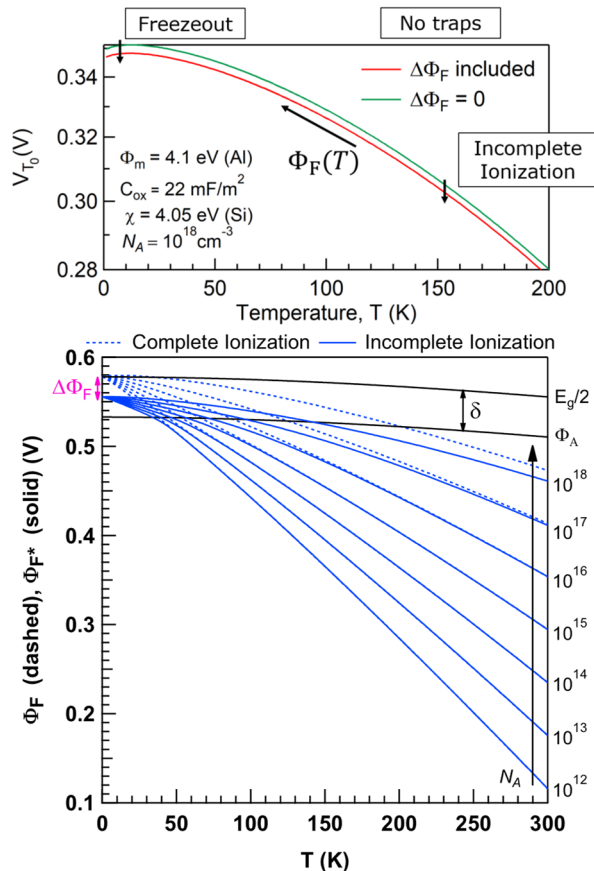
■ Current dominated by SDT at CT

■ Current dominated by hopping current I_{hop_2} at CT

Outline

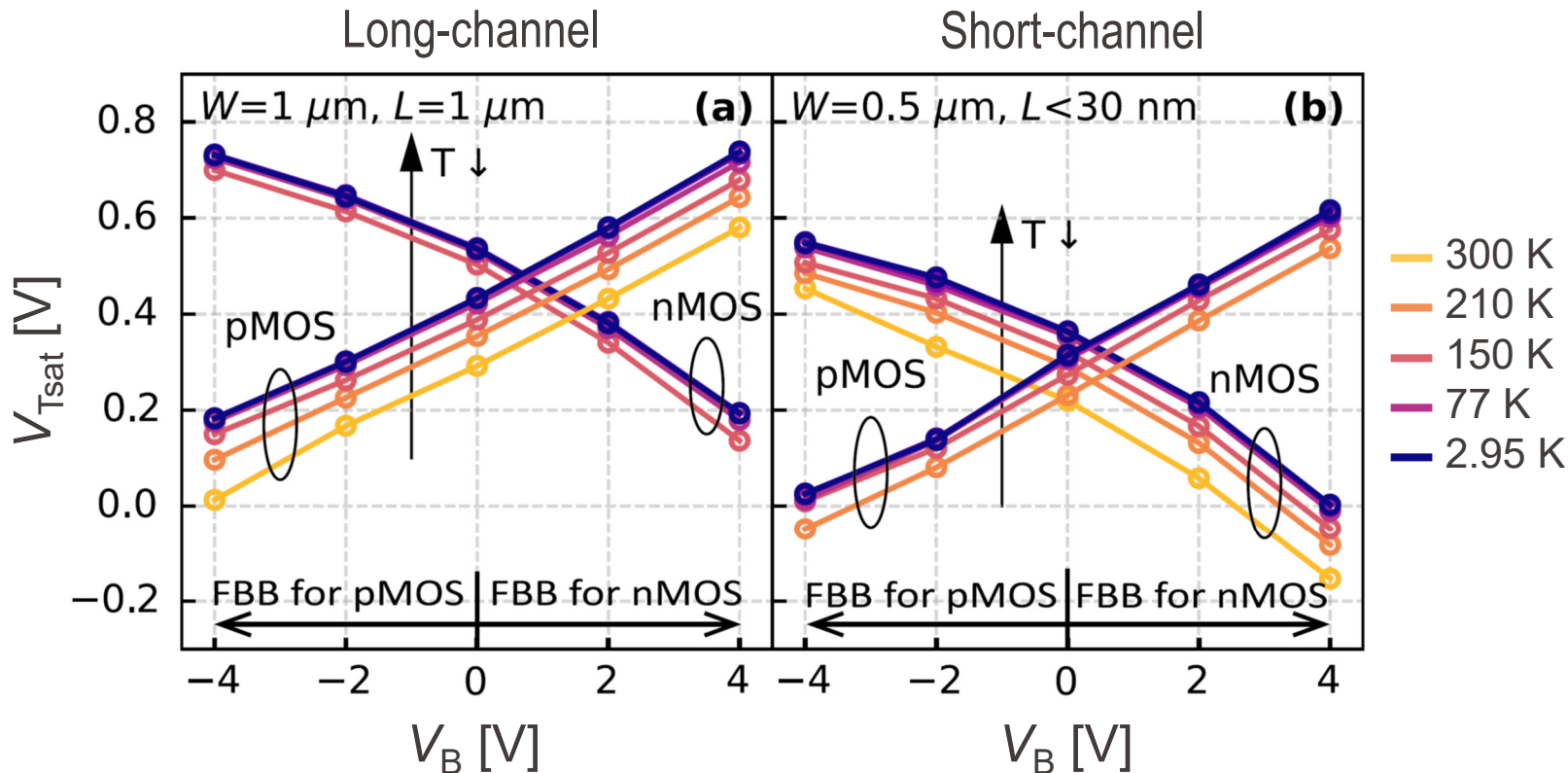
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Threshold Voltage Modeling



- ΔV_{T0} mostly due to change in the Fermi voltage as illustrated in the right figure
- Impact of incomplete ionization is minor

Threshold Voltage vs Back-gate Voltage



- Introduction
- Subthreshold current and swing
- Threshold voltage
- **Simplified EKV model at CT**
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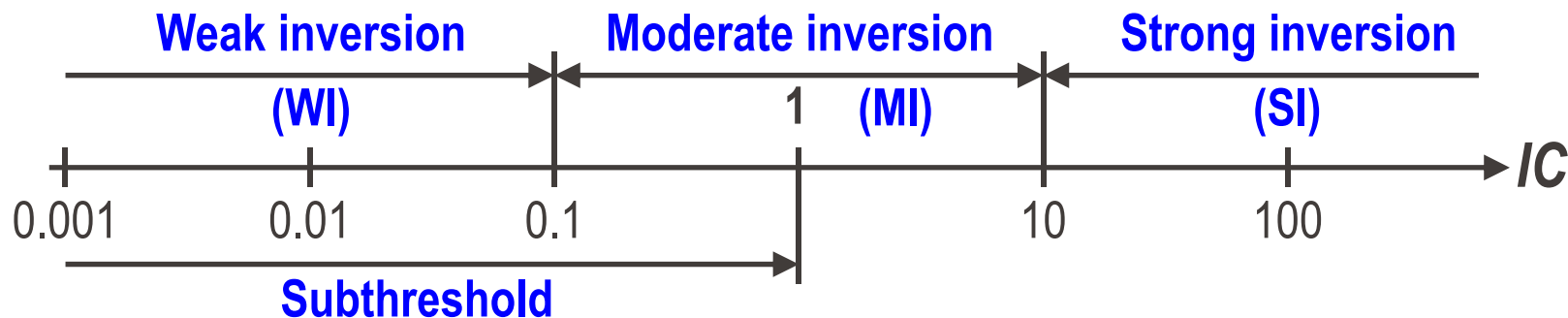
The Concept of Inversion Coefficient

- Overdrive voltage $V_G - V_{T0}$ not convenient for weak inversion
- Replaced by the **inversion coefficient IC** characterizing the global level of inversion of the transistor in **saturation**

$$IC \triangleq \frac{I_D|_{\text{saturation}}}{I_{spec}}$$

Typical values of $I_{spec\Box}$ for 28-nm (at RT):
750 nA for NMOS
200 nA for PMOS

- where $I_{spec} = I_{spec\Box} \cdot W/L$, $I_{spec\Box} \triangleq 2n \cdot \mu \cdot C_{ox} \cdot U_T^2$, $U_T \triangleq kT/q$



Simplified EKV Charge-based Model (in saturation)

- The **normalized drain current** in saturation or **inversion coefficient** is given by

$$IC \triangleq \frac{I_D|_{saturation}}{I_{spec}} = \frac{4(q_s^2 + q_s)}{2 + \lambda_c + \sqrt{4(1 + \lambda_c) + \lambda_c^2 \cdot (1 + 2q_s)^2}}$$

- where $q_s \triangleq Q_i(x = 0)/Q_{spec}$ is the **normalized inversion charge** at the source with $Q_{spec} \triangleq -2n \cdot C_{ox} \cdot U_T$
- λ_c is the **velocity saturation** (VS) parameter corresponding to the fraction of the channel under full velocity saturation

$$\lambda_c \triangleq \frac{L_{sat}}{L}$$

- where $L_{sat} = 2\mu_0 \cdot U_T / v_{sat} = 2U_T / E_c$ is the channel length over which the velocity is fully saturated

Voltage versus Charge

- The current versus charge expression is coupled to the following **voltage versus charge** relation

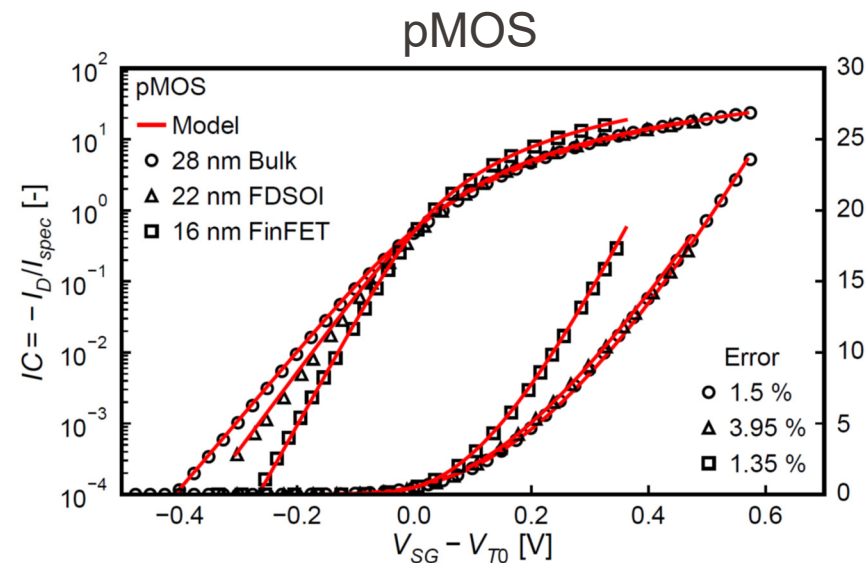
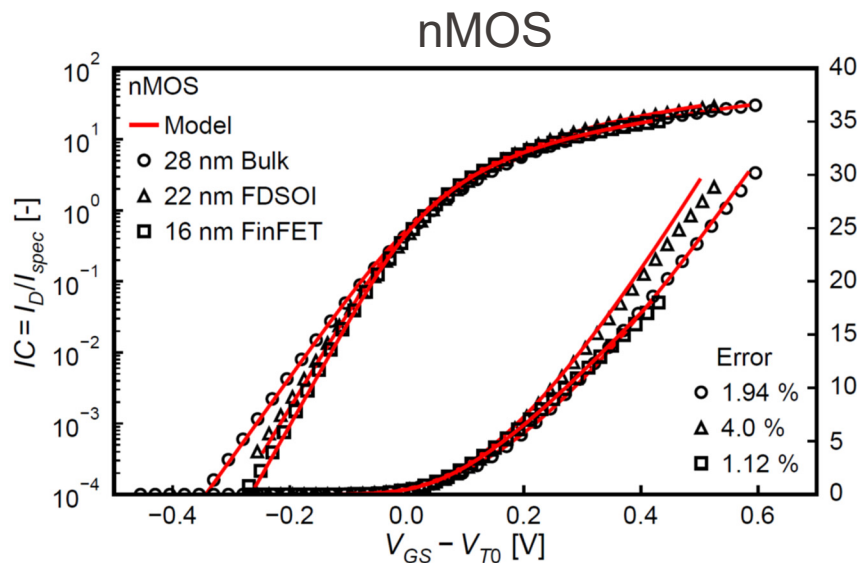
$$v_p - v_s = \ln(q_s) + 2q_s$$

- where voltages are normalized to $U_T \triangleq kT/q$

$$v_p \triangleq \frac{V_P}{U_T} = \frac{V_G - V_T}{n \cdot U_T} \quad v_s \triangleq \frac{V_S}{U_T} \quad U_T \triangleq \frac{kT}{q}$$

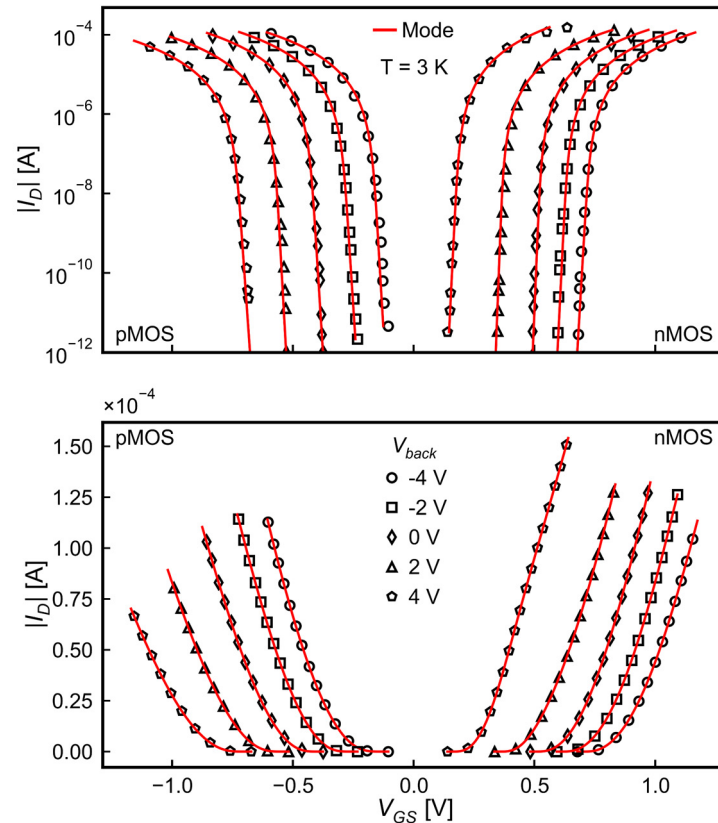
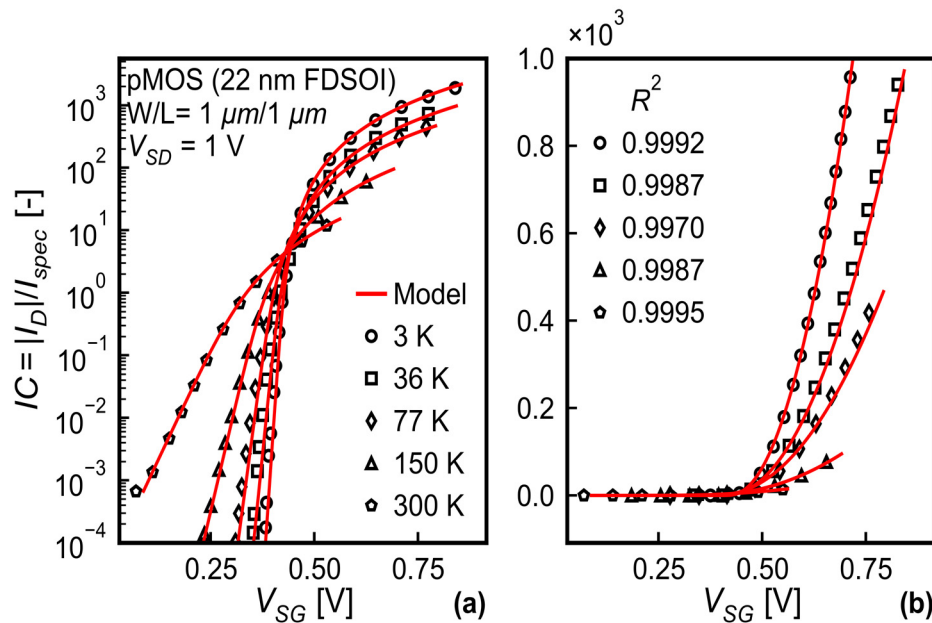
- where $V_P = (V_G - V_T)/n$ is the **pinch-off voltage**
- Only requires the following **4 parameters**: V_T , $I_{spec\Box}$, n , L_{sat} (or λ_c)
- No explicit expression of the current versus voltage
- Note that parameter n allows to change the slope factor versus temperature

sEKV for Different Advanced Technologies (RT)

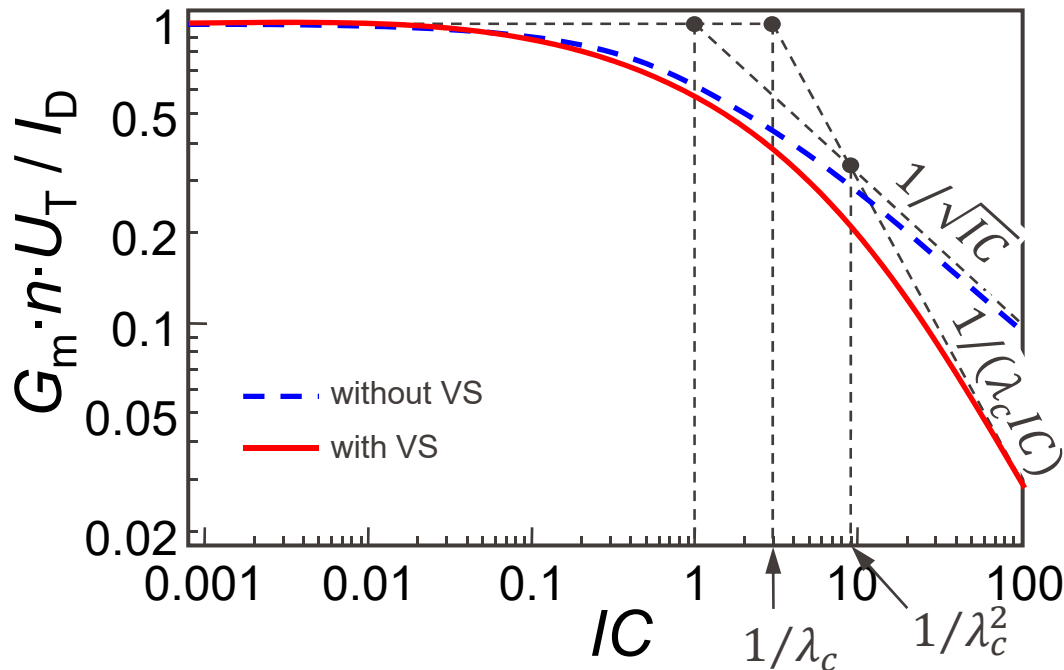


- The normalization process strips-off most of the technology dependence which is captured by only **4 parameters** V_{T0} , I_{spec} , n , L_{sat}

sEKV for 22nm FDSOI at Cryogenic Temperature



Current Efficiency or G_m/I_D FoM

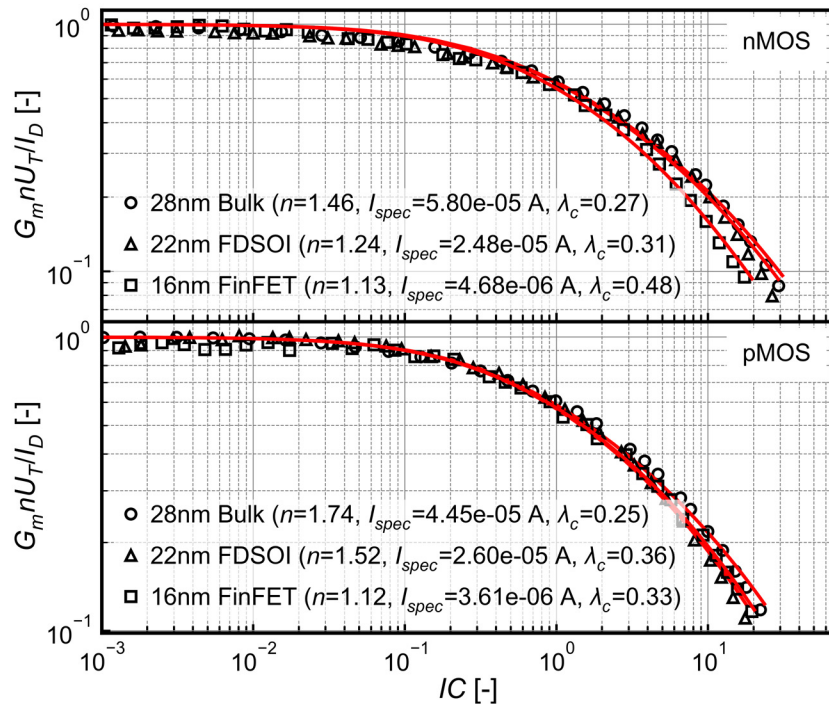


$$\begin{aligned} \frac{g_{ms}}{i_d} &\triangleq \frac{G_{ms} \cdot U_T}{I_D} = \frac{G_m \cdot n \cdot U_T}{I_D} \\ &= \frac{\sqrt{(\lambda_c IC + 1)^2 + 4IC} - 1}{IC \cdot [\lambda_c \cdot (\lambda_c IC + 1) + 2]} \\ &= \begin{cases} 1 & \text{WI and sat.} \\ \frac{1}{\lambda_c \cdot IC} & \text{SI and sat.} \end{cases} \\ \lambda_c &\triangleq \frac{L_{sat}}{L} \end{aligned}$$

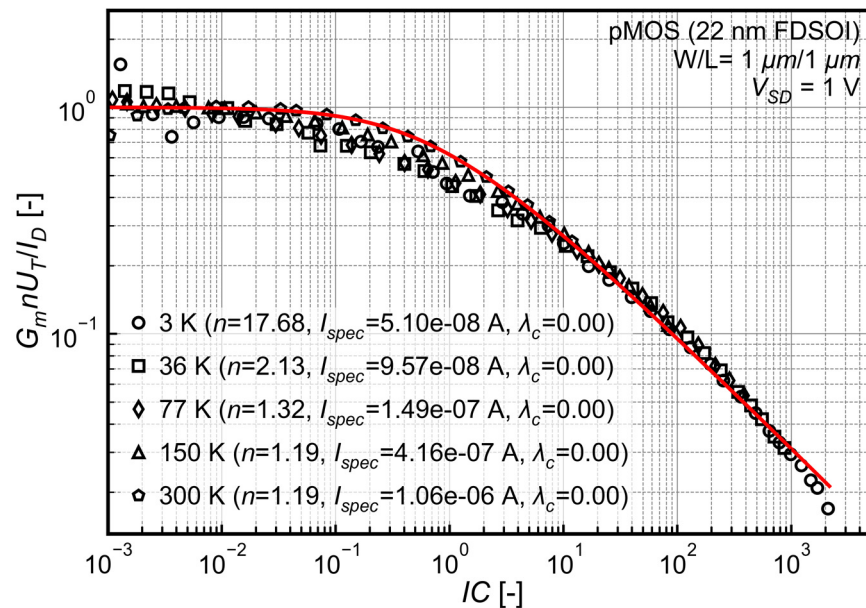
- The G_m/I_D FoM tells how much G_m you get for a given current
- It is a fundamental FoM for low-power analog and RF IC design

The G_m/I_D for Different Advanced Technologies

RT



RT down to CT

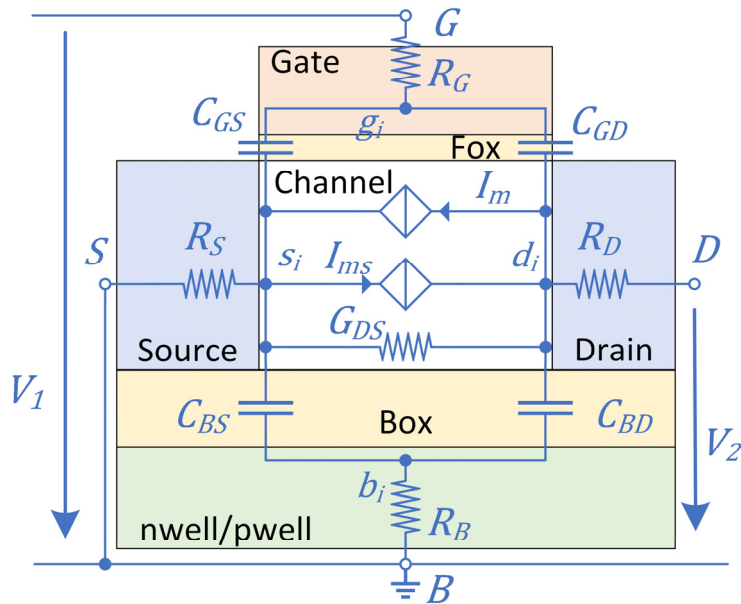


The normalized G_m/I_D FoM is **invariant to technologies**

The normalized G_m/I_D FoM is almost **independent of temperature**

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Simple RF modeling of FDSOI



- Approximation of the Y -parameters given below
- $\Re(Y)$ shows quadratic behavior with respect to frequency
- It allows direct analytical parameter extraction (without optimization)

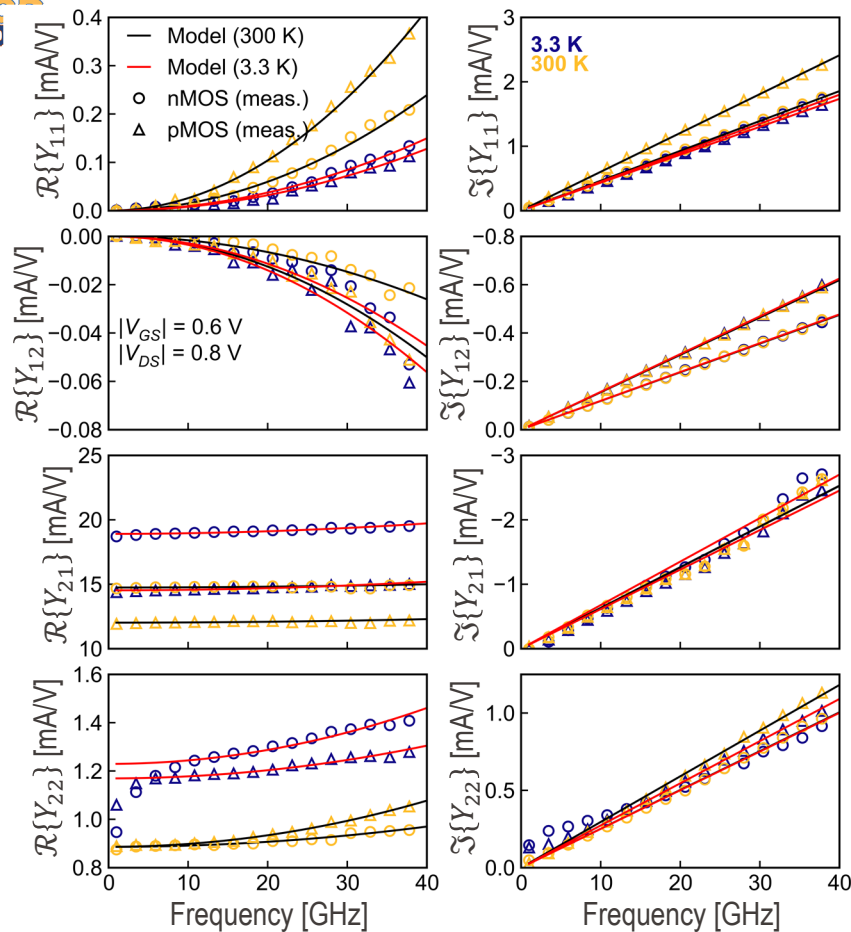
$$Y_{11} \cong \omega^2(C_{GB}^2 R_B + C_{GG}^2 R_G) - j\omega C_{GG}$$

$$Y_{12} \cong \omega^2(C_{BD} C_{GB} R_B - C_{GD} C_{GG} R_G) - j\omega C_{GD}$$

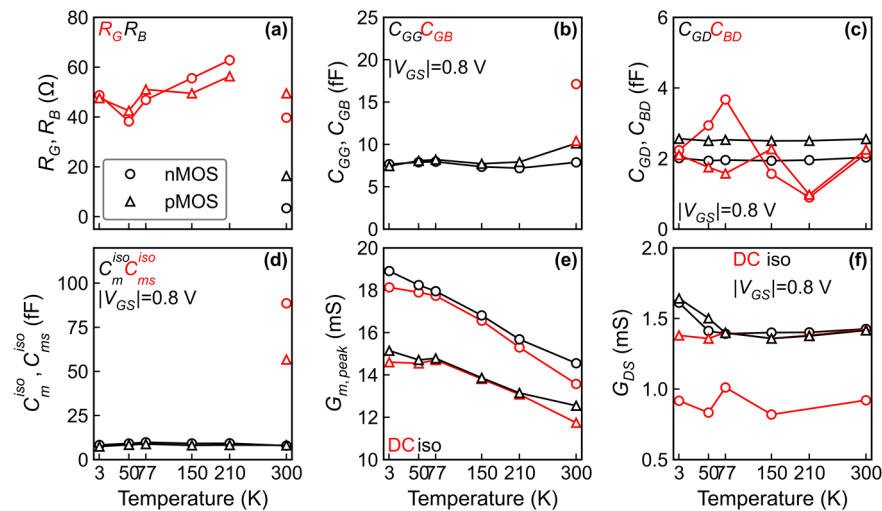
$$Y_{21} \cong G_m + \omega^2[C_{GB} R_B (C_{BD} - C_m + C_{ms}) - C_{GG} R_G (C_{GD} + C_m)] - j\omega (C_{GD} + C_m)$$

$$Y_{22} \cong G_{ds} + \omega^2[C_{BD} R_B (C_{BD} - C_m + C_{ms}) + C_{GD} R_G (C_{GD} + C_m)] + j\omega (C_{BD} + C_{GD})$$

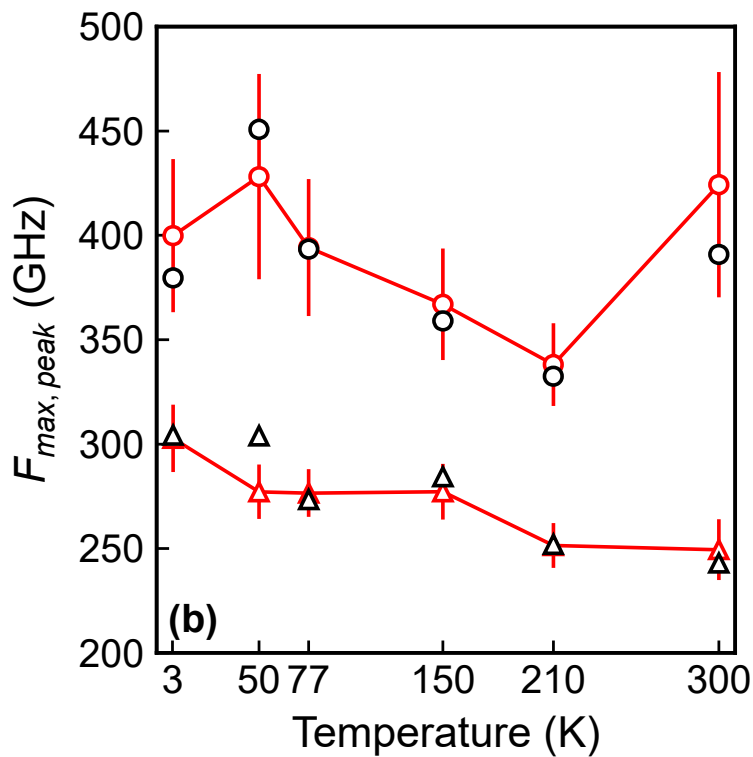
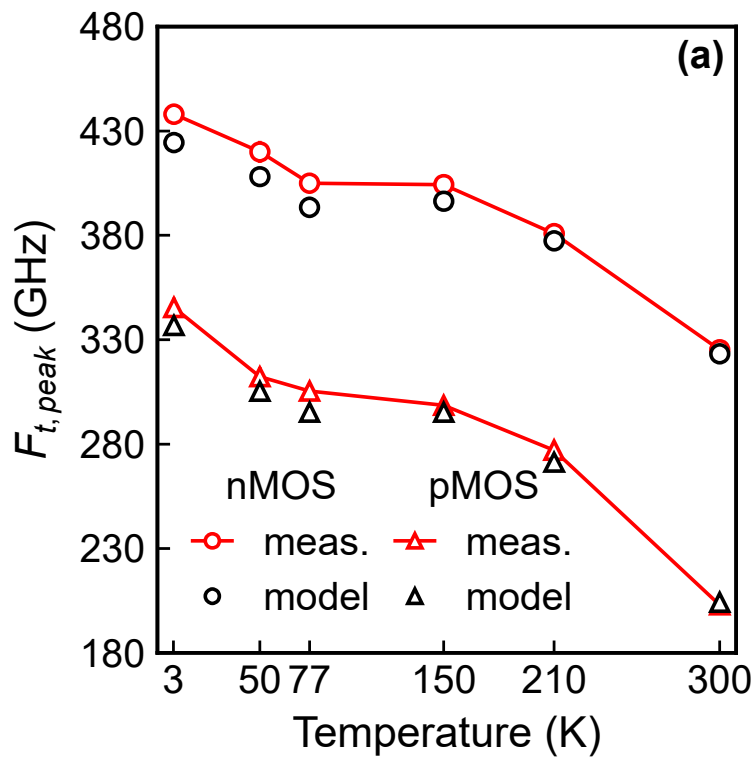
RF Extraction Compared to Measurements (RT & CT)



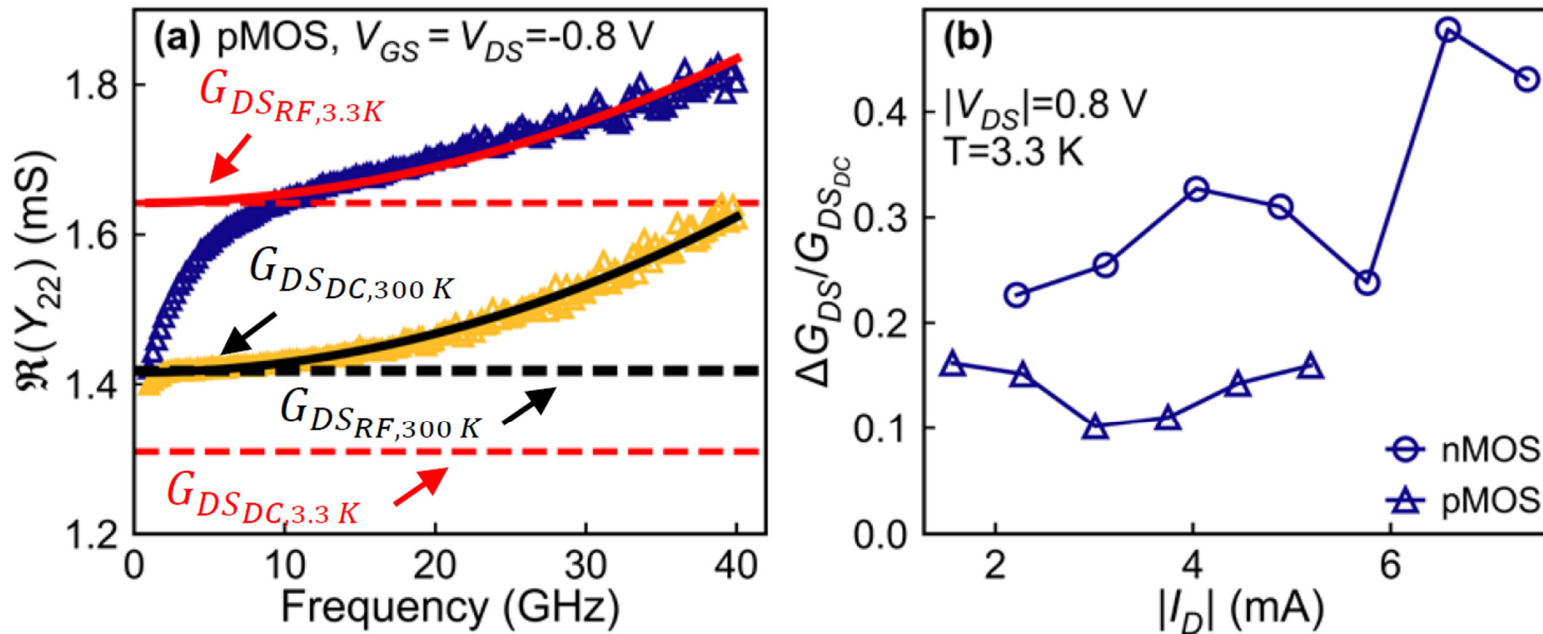
Extracted parameters versus temperature



$F_{t,peak}$ and F_{max} versus Temperature

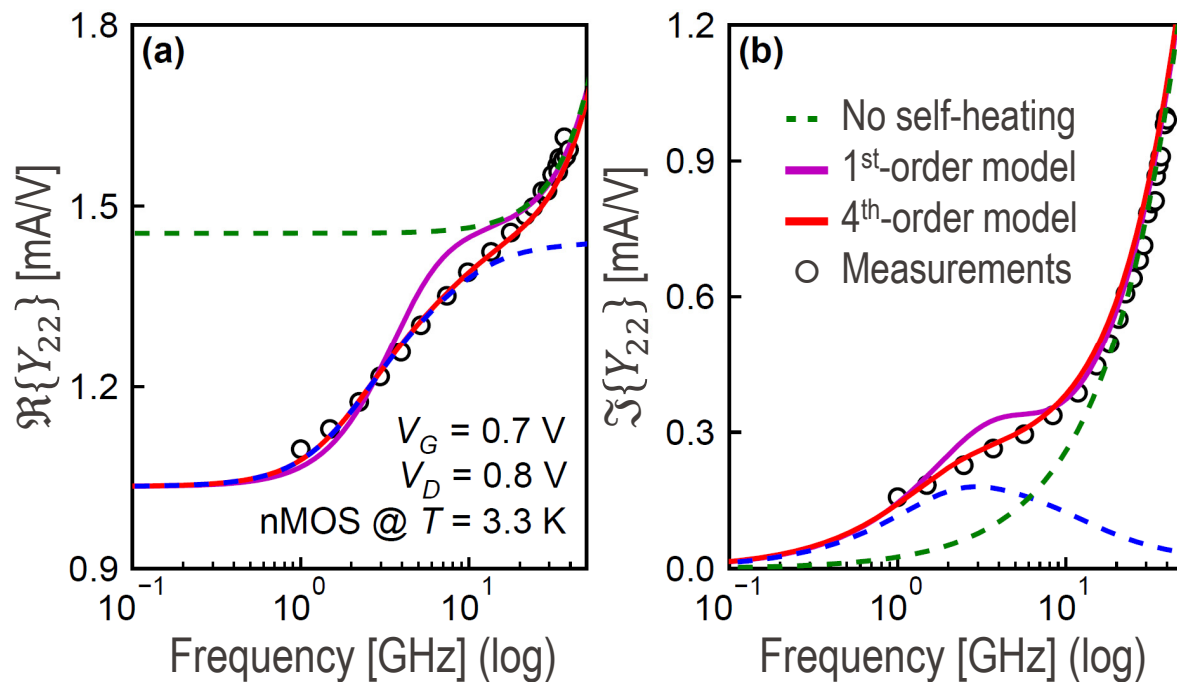


Impact of Self-heating on $\Re(Y_{22})$



- The non-quadratic behavior of $\Re(Y_{22})$ at low frequency is due to **self-heating**
- The difference between G_{DSRF} and G_{DSDC} is due to self-heating and becomes significant at 3.3 K particularly for nMOS

Y-parameters at CT including Self-Heating

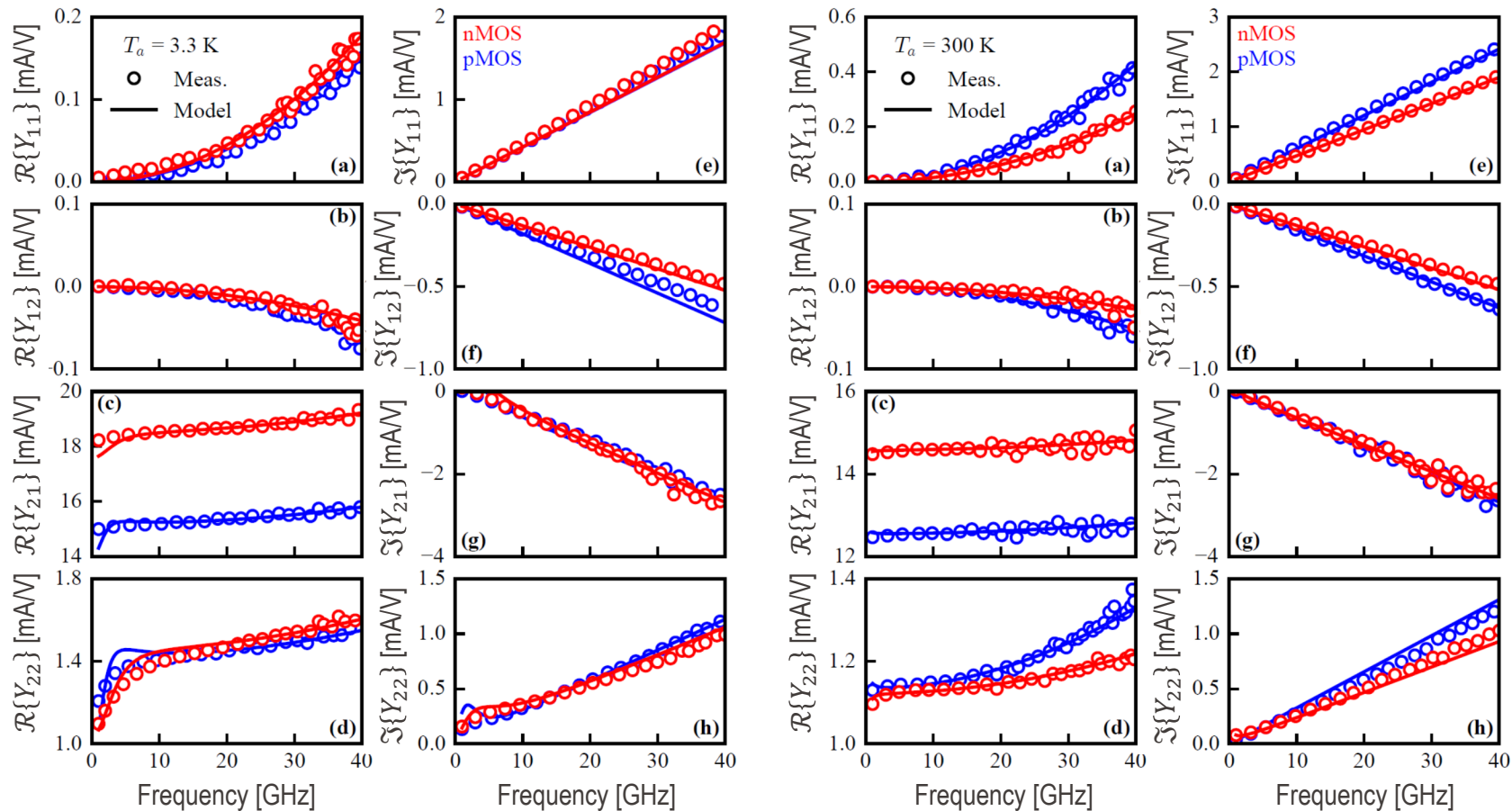


$$Y^{RF} = Y^{NW} + Y^{SH}$$

- Y^{NW} iso-thermal Y-param.
- Y^{SH} dynamic SH term

- A 4th-order thermal network is needed for a proper modeling of the dynamic SH effect

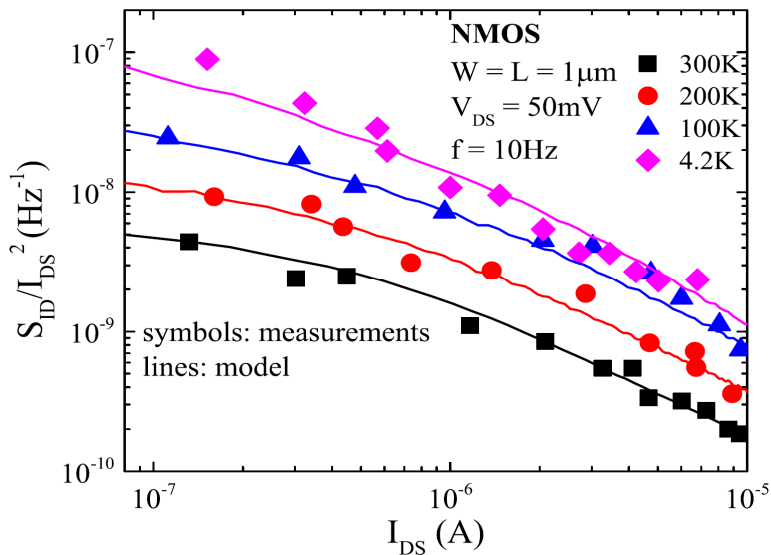
Y-Parameters at RT and CT (incl. SH)



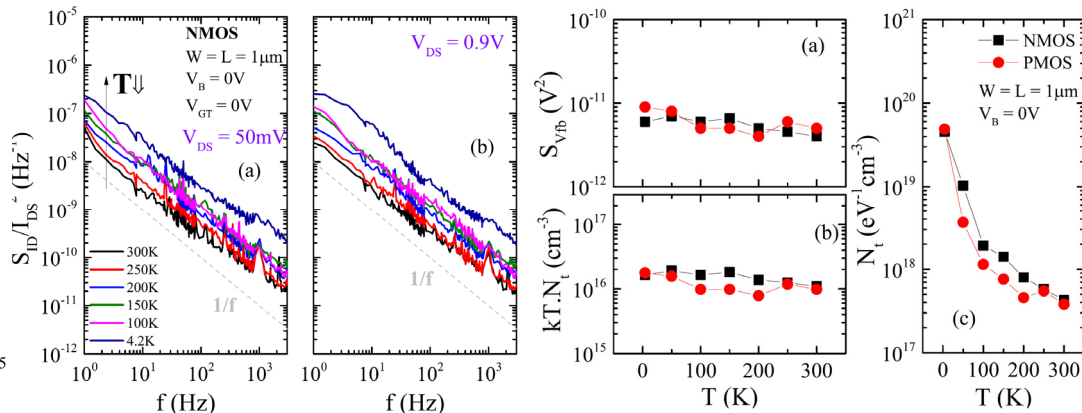
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Low-frequency Noise in 22nm FDSOI



$$\frac{S_{ID}}{I_{DS}^2} = \left(\frac{G_m}{I_{DS}}\right)^2 \cdot \left(1 + \Omega \frac{I_{DS}}{G_m}\right)^2 \cdot S_{V_{fb}} \text{ with } S_{V_{fb}} = \frac{q^2 kT \lambda N_t}{W L C_{ox}^2 f}$$



- The noise-to-signal ratio S_{ID}/I_{DS}^2 increases at CT thanks to improved G_m/I_{DS} at CT (in strong inversion)
- The simple model fits the data well down to CT
- Parameter $\Omega \cong 4 \text{ V}^{-1}$ and $S_{V_{fb}}$ are almost temperature independent

White Noise and the Fano Noise Suppression Factor

- The **Fano noise suppression factor** compares the PSD of the drain current fluctuations to the PSD of shot noise which is dominant in weak inversion

$$F_a = \frac{S_{\Delta I_D^2}}{2qI_D} = \frac{4k_B T \cdot \gamma_n G_m}{2qI_D} = 2U_T \cdot \gamma_n \cdot \frac{G_m}{I_D} = 2 \frac{\gamma_n}{n} \cdot \frac{g_{ms}(IC)}{IC}$$

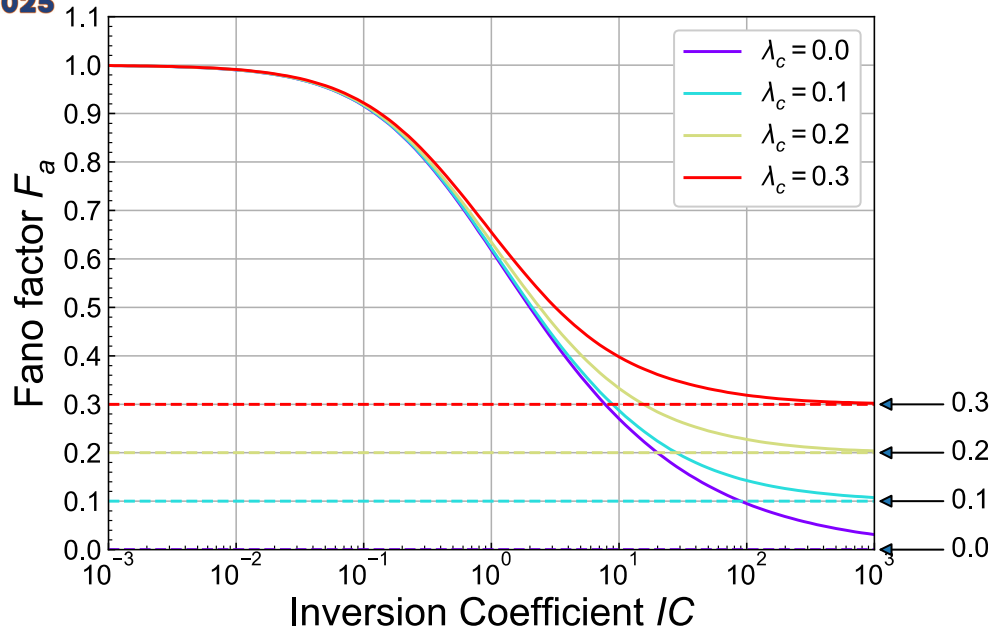
- By definition $F_a = 1$ when the noise is **full shot noise** like in weak inversion and $F_a < 1$ when the noise is only **partially** due to shot noise like it is the case in moderate and strong inversion for example
- The Fano noise suppression factor is actually **proportional to the G_m/I_D ratio**
- It can be expressed in terms of the inversion coefficient IC by using the **normalized G_m/I_D ratio**

$$\frac{g_{ms}(IC)}{IC} = \frac{G_m nU_T}{I_D} = \frac{\sqrt{4IC + 1 + (\lambda_c IC)^2} - 1}{IC (2 + \lambda_c^2 IC)}$$

EPFL The Fano Factor versus IC for Short Channel Transistors

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- For short-channel

$$F_a \cong (1 + \lambda_c^2 \cdot IC) \cdot \frac{g_{ms}(IC)}{IC}$$

- where $\lambda_c \triangleq \frac{L_{sat}}{L}$

- with $L_{sat} = \frac{2\mu_0 \cdot U_T}{v_{sat}} = \frac{2U_T}{E_c}$

- In strong inversion

$$F_a \cong \lambda_c$$

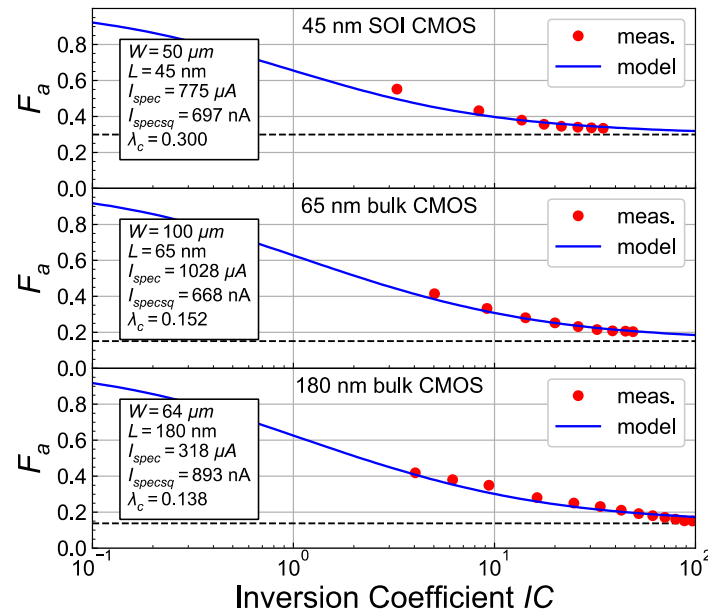
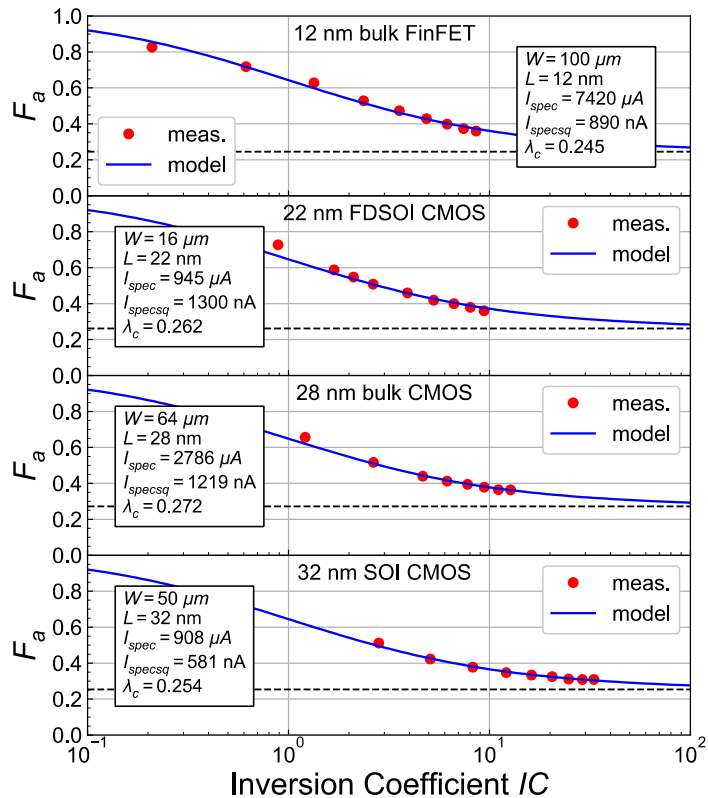
- In weak inversion

$$F_a \cong 1$$

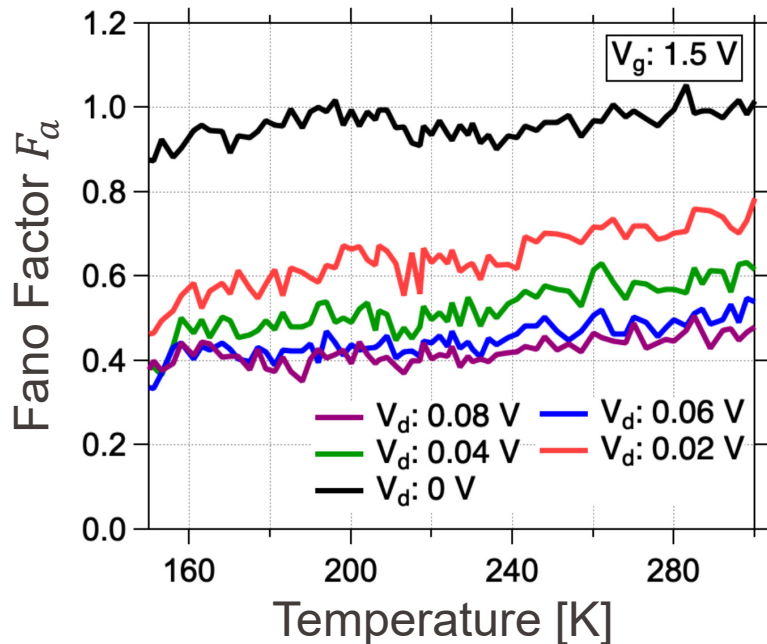
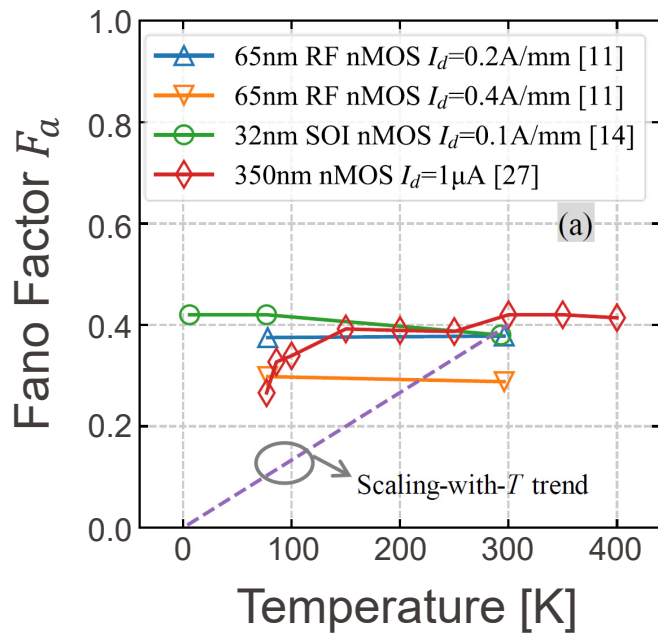
- The Fano noise suppression factor is limited to λ_c in strong inversion



Fano Factor Measured on Several Technologies (RT)



Fano Suppression Factor F_a versus Temperature



- Like the normalized G_m/I_D , the Fano noise suppression factor F_a is almost **temperature independent**, but depends on the inversion coefficient IC

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- Available CMs do not scale correctly with T down to CT
- Most MOSFET DC features improve at CT except
 - V_{T0} which increases
 - SS which saturates
 - Additional hopping and tunneling subthreshold currents appear for short-channel at high V_{DS} voltage
- The sEKV can do a good job modeling silicon devices at CT
- RF Y -parameters can be properly modelled at CT, but self-heating needs to be accounted for in $\Re(Y_{22})$
- The white noise can be modelled with the Fano noise suppression factor taking advantage of the temperature independence of the normalized G_m/I_D FoM

Additional Resources

- Github page of Christian Enz:

<https://github.com/chrisenz>

- General analog circuit design:

<https://github.com/chrisenz/Analog-Circuit-Design>

- Currently including:

- [Optimization of capacitive closed loop CS amplifier](#)
- [AC simulation of SC circuits with a standard Spice simulator](#)
- And many more to come...

Thank you

Christian Enz
Hung-Chi Han
Edoardo Charbon